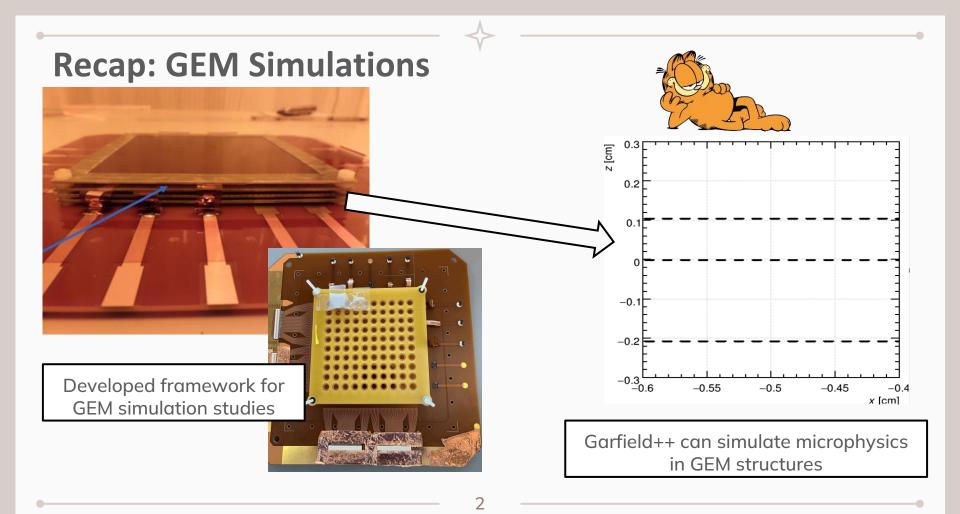
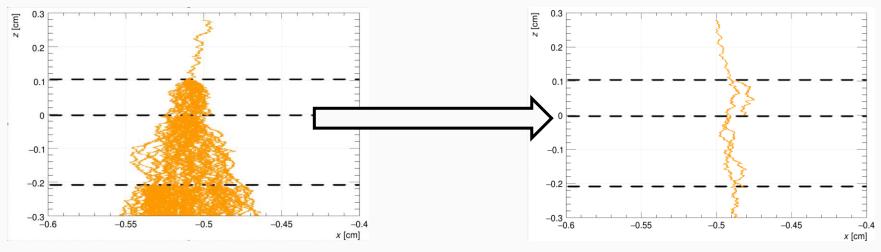


ND-GAr Meeting Update 12/17/2024

Brenna McConnell, Indiana University



Previous Results: GEMs in High Pressure

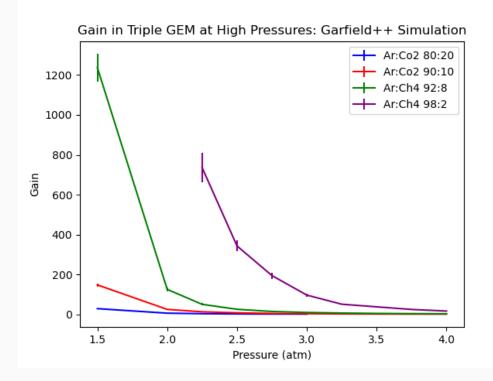


Avalanche – Ar:Co2 80:20, 1 atm

Avalanche – Ar:Co2 80:20, 2 atm

Increasing the pressure decreases mean free path of electron \rightarrow **reduces gain**

Previous Results: Effect of Gas Mixture

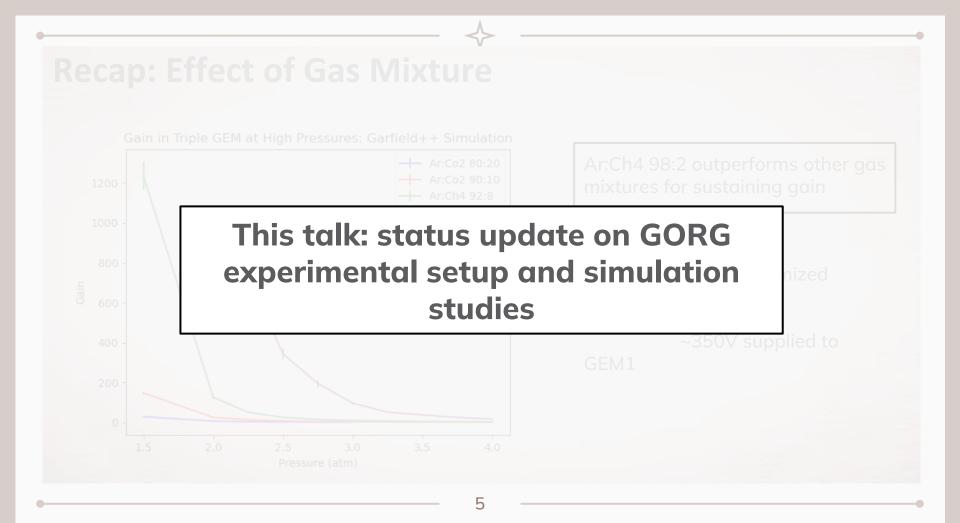


Ar:Ch4 98:2 outperforms other gas mixtures for sustaining gain

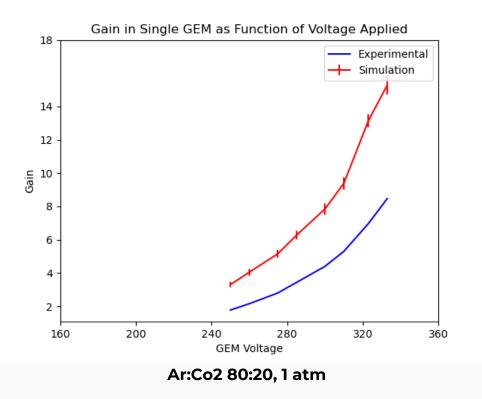
Note: plot is for unoptimized parameters:

~350V supplied to GEM1

~E∏ ≈ 6.0kV/cm



Benchmarking: Voltage Applied

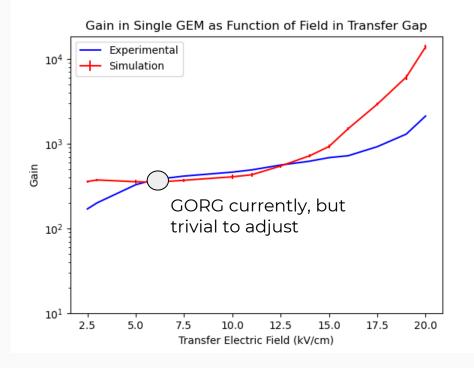


- ★ Simulation results overestimate but agree within a <u>factor of 2</u>
- Experimental data from:

High Energy Phys. 2016, 8561743. DOI: 10.1155/2016/8561743

~E_I = 1kV/cm ~Induction gap = 8.5mm

Benchmarking: Electric Field Strength



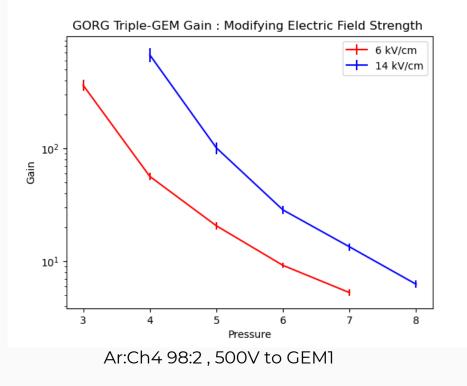
 ★ For a single GEM with:
Ar:CO₂ 70:30 l atm 500V across GEM 0.5mm induction gap

demonstrates up to an **18-fold** increase in gain!

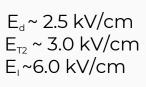
Experimental results from:

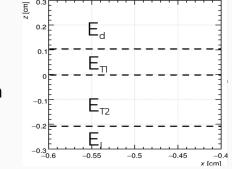
A. Bondar, et al., Nuclear Instruments and Methods A 419 (1998) 418.

GORG Simulations: Electric Field Strength



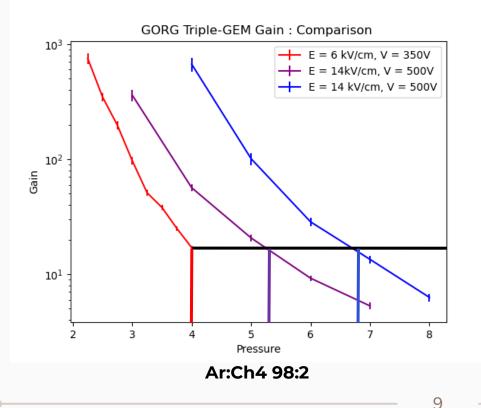
• Electric field strength modified only in transfer gap between GEM1 and GEM2:





- an increased 500V to GEM1
- Can increase achievable gain at high pressures!

Comparison with Previous Results



E_d ~ 2.5 kV/cm E_{T2} ~ 3.0 kV/cm E₁ ~6.0 kV/cm

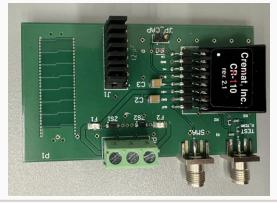
- Achieve similar gains at ~+3 atm!
- More to optimize:
 - Transfer gaps
 - GEM geometry: pitch, thickness, hole diameter

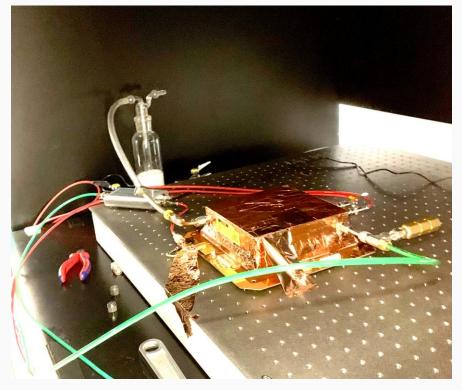
Electronics Upgrades Underway

Full chain of electronics under development by Imperial colleagues



Low Noise Cremat II Card being tested at FNAL





Summary

- Benchmarked simulation results with established experimental data
- Evaluated the effect of electric field strength on GEM gain
 - Other parameters that can be optimized in simulation to further increase gain:
 - Transfer gaps
 - GEM pitch
 - GEM hole diameter
- Progress experimentally in electronics upgrades; preparing for pressure vessel operation at Fermilab, setup underway at Indiana University!